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It is a great honor to have a presentation opportunity related to EUV optical development in the KISM adv.Litho division. In this presentation, I would like to share the development status and contents of the high efficiency EUV Zone plate, which is a key element for EUV equipment.

I am currently developing EUV optical elements as a VP of ESOL R&D center with background of eBeam/Photo Litho., EDA (OPC/RET/MPC) and EUV optics development specialist. My Brief Biograph is as follows.

Summary of qualification

eBeam/ Photo Litho., EDA(OPC/RET/MPC) and EUV optics development specialist

- EUV solution development (EUV source, Optic and system engineering)
- OPC, RET, Photo Litho, Ebeam Litho & Semiconductor process
- Foundry & Memory EDA R&D OPC/RET application development coordinator

Carrier

2000.01.03 ~ 2015.09 : Samsung Electronics R&D center

- Photomask team : Ebeam Litho. & Process
- R&D Photo team : Photo Litho. Technical Leader
- Process Dev.team : OPC team Memory device RET/OPC Technical Leader

2015.10 ~ 2022.05: Siemens EDA, RET/OPC sr.Manager(상무) of Korea team

2022.06 ~ : ESOL R&D center, Development leader of EUV Optics Vice President(상무)

Key Performance Activities

[Samsung R&D center Mask] Development of CAR process (2003)

[Samsung R&D center Photo] Development of sub-nm grid OPC (2005)

[Samsung R&D center Photo] Development of DPT process (2007)

[Siemens EDA] Lead developments of OPC Application development (2016~)

[Siemens EDA] Lead developments of hybrid-OPC and EUV curve-linear OPC or ILT for Fullchip, FullMask solution with new algorithm(2021)

[Siemens EDA] Development of sILT(simple-I Mentor LT) for Memory Fullchip random Core/Peri. layer ILT solution(2020)

[Siemens EDA] JSFOPC(JigSaw Flow) development(2018)

[Siemens EDA] CAOPC(Cell array OPC) flow program(2016)